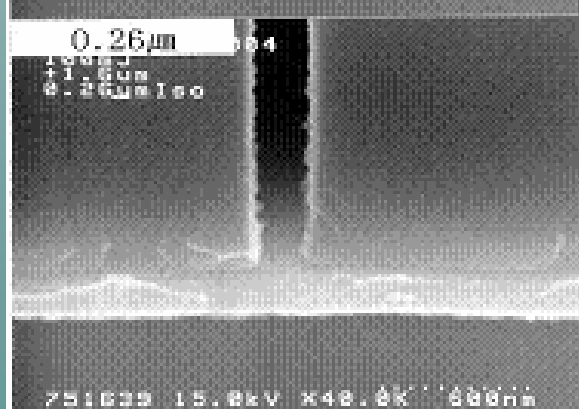
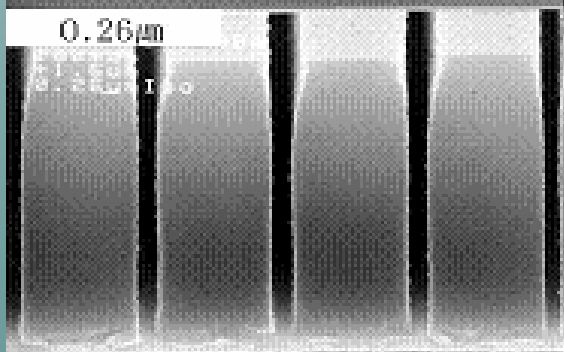
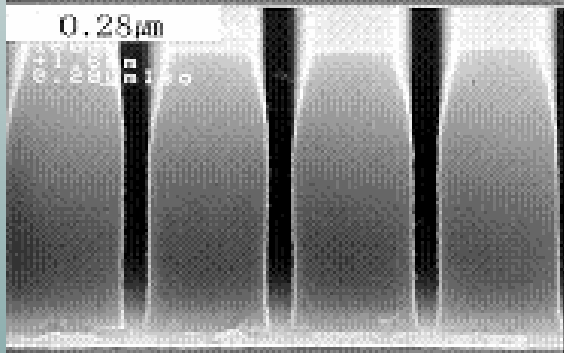
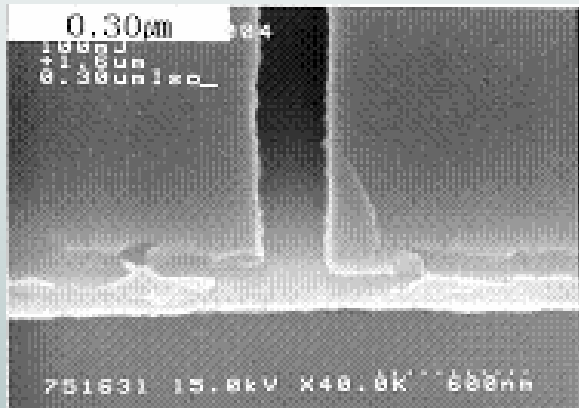
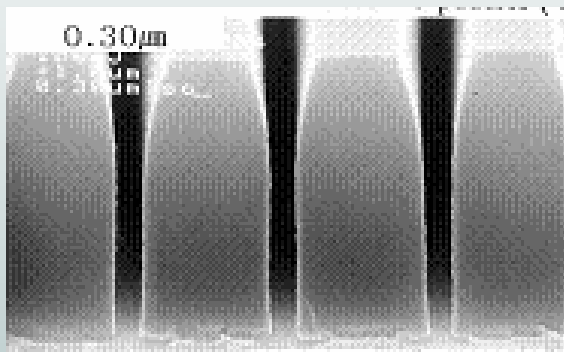
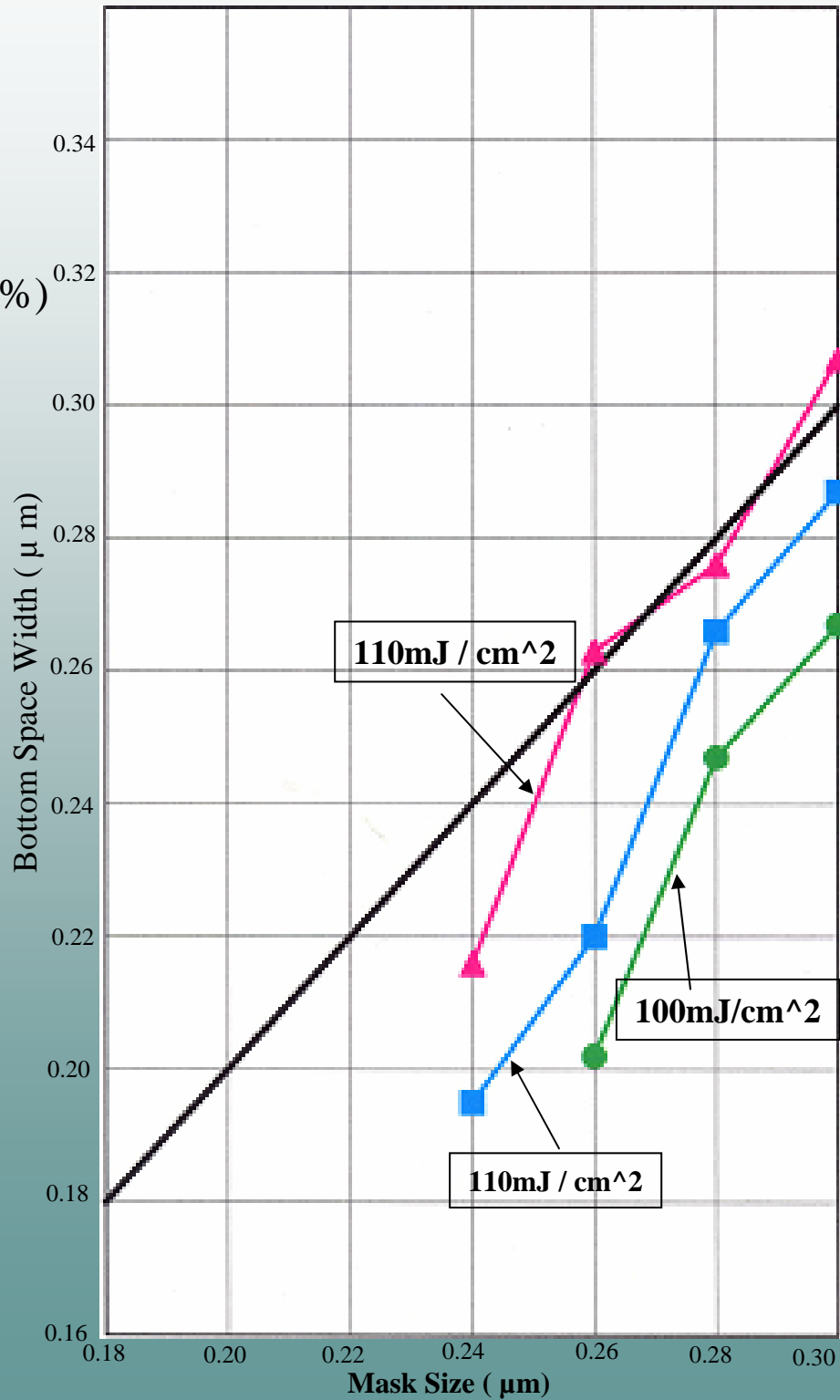


Film Thickness: 4.0 μ m
Prebake: 120°Cx240 sec
Exp.: 100mJ/cm² (NSR-2005Ex8A , NA = 0.50, $\sigma = 0.70$)

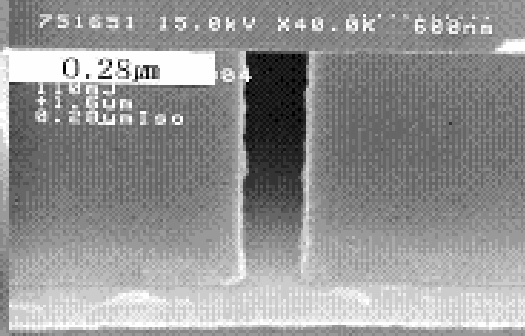
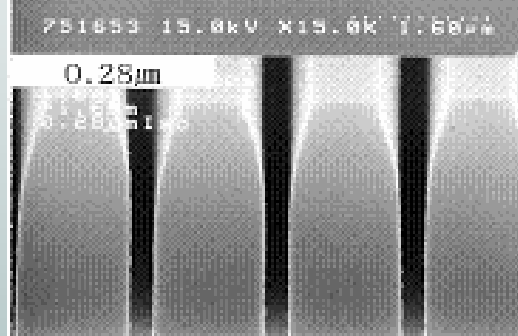
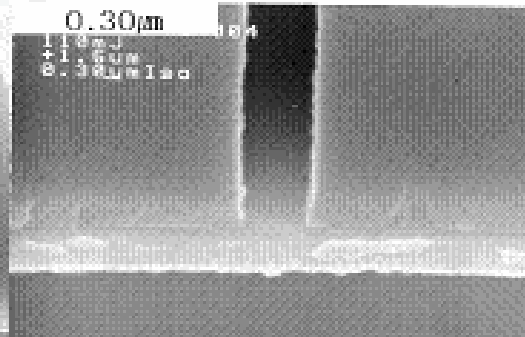
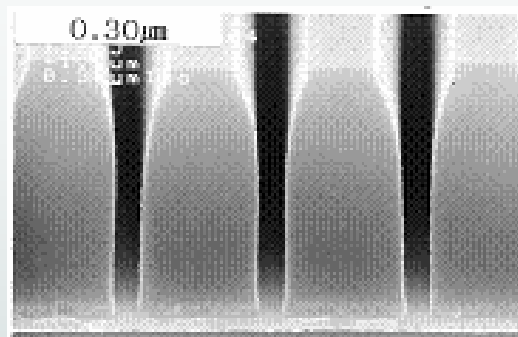
Mask: 0.30 – 0.24 μ m
Focus: +1.6 μ m
PEB: 100°C x 120 sec
Dev.: 50 sec x 3 puddles (SSFD-238)



PB: 120°C x 240 sec
PEB: 100°C x 120 sec
Dev: 50 sec x 3 times
(SSFD-238 TMAH =2.38%)



Film Thickness: 4.0 μm
 Prebake: 120°C x 240 sec
 Exp.: 100 mJ/cm² (NSR-2005Ex8A, NA = 0.50, σ = 0.70)
 Mask: 0.30 – 0.24 μm
 Focus: +1.6 μm
 PEB: 100°C x 120 sec
 Dev.: 50 sec x 3 puddles (SSFD-238)



Film Thickness: 4.0 μ m
 Prebake: 120°C x 240 sec
 Exp.: 120mJ/cm²
 (NSR-2005Ex8A ,
 NA = 0.50, σ = 0.70
 Mask: 0.30 – 0.24 μ m
 Focus: +1.6 μ m
 PEB: 100°C x 120 sec
 Dev.: 50 sec x 3 puddles
 (SSFD-238)

